

Please replace the paragraph beginning on page 7, line 3, with the following rewritten paragraph:

5.22.09

According to a second aspect of the present invention, there is provided an exposure apparatus (EX) which exposes a substrate (P) by radiating an exposure light beam (EL) onto the substrate (P) through a liquid (LQ); the exposure apparatus comprising a mover (PST) which holds the substrate; a driving unit (PSTD) which moves the mover (PST); and a control unit (CONT) which controls the driving unit (PSTD) and includes first control information to move the mover (PST) in the presence of the liquid (LQ) supplied onto the mover (PST), and second control information to move the mover (PST) in the absence of the liquid (LQ) supplied onto the mover (PST).

Please replace the paragraph beginning on page 7, line ~~10~~, with the following rewritten paragraph:

According to a third aspect of the present invention, there is provided a position control method for controlling a position of a mover (PST) by using a reflecting surface (MX, MY) formed on the mover (PST) which holds a substrate (P) in an exposure apparatus (EX) for exposing the substrate (P) by radiating an exposure light beam (EL) onto the substrate (P) through a liquid (LQ); the position control method comprising measuring error information about an error of the reflecting surface (MX, MY) in the presence of the liquid (LQ) supplied onto the mover (PST); and controlling the position of the mover (PST) on the basis of the error information.

Please replace the paragraph beginning on page 8, line 10, with the following rewritten paragraph:

5.22.09

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